

## ABSTRACT

SUBSTRATE HOLDING APPARATUS, SUBSTRATE POLISHING APPARATUS,  
ELASTIC MEMBER, AND MANUFACTURING METHOD OF SUBSTRATE HOLDING  
APPARATUS

Provided is a substrate holding apparatus comprising: a top ring main body; an elastic film comprising a first surface and a second surface, the first surface forming a plurality of areas between the first surface and the top ring main body, the second surface being located opposite to the first surface and capable of holding a substrate; a first line that communicates with a first area among the plurality of areas and can pressurize the first area; a second line that communicates with the first area and can exhaust air from the first area; a measuring instrument whose measurement value varies based on a flow rate of the first area; a third line that communicates with a second area different from the first area among the plurality of areas and can depressurize the second area; and an elastic member provided between the first line and the second line so as to be separated from the first surface of the elastic film when the second surface of the elastic film does not hold a substrate and be in contact with the first surface of the elastic film when the second surface of the elastic film holds a substrate.

Figure 6A